AMENDMENTS TO THE CLAIMS:

Please cancel claim 18 without prejudice. Please amend claims 1, 3, 9, 11, 19-21, and

28-30 as follows.

1. (currently amended) An apparatus, comprising:

a first optical waveguide disposed in a semiconductor material layer, the first optical

waveguide including a first charge layer;

a second optical waveguide disposed in the semiconductor material layer, the second

optical waveguide including a second charge layer; and

an insulating region disposed between the first and second optical waveguides to provide

a coupling region in the semiconductor material layer between the first and second optical

waveguides, the first charge layer and the second charge layer formed proximate to the insulating

region, the coupling region having a first coupling length for a first polarization mode of an

optical beam directed through one of the first and second optical waveguides into the coupling

region, the coupling region having a second coupling length for a second polarization mode of

the optical beam.

2. (original) The apparatus of claim 1 wherein the first polarization mode of the optical

beam is directed out from the coupling region through the first optical waveguide and the second

polarization mode of the optical beam is directed out from the coupling region through the

second optical waveguide.

3. (currently amended) The apparatus of claim 2 wherein a wherein propagation of the

optical beam through the first and second optical waveguides is bi-directional.

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4. (original) The apparatus of claim 1 wherein the semiconductor material layer includes

silicon.

5. (original) The apparatus of claim 1 wherein the insulating region includes an oxide.

6. (original) The apparatus of claim 1 wherein the first and second optical waveguides

comprise single mode optical waveguides.

7. (original) The apparatus of claim 1 wherein said optical beam directed through said

one of the first and second optical waveguides into the coupling region comprises unpolarized

light.

8. (original) The apparatus of claim 1 wherein the coupling region comprises two single

mode asymmetric waveguides separated by the insulating region, the two single mode

asymmetric waveguides including the first and second optical waveguides.

9. (currently amended) The apparatus of claim 1 further comprising modulated charge

layers proximate to the insulating region in the coupling region to wherein the first and second

charge <u>layers</u> adjust the first and second coupling lengths.

10. (original) The apparatus of claim 1 wherein the first polarization mode of the optical

beam comprises a transverse magnetic field (TM) mode of the optical beam and the second

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polarization mode of the optical beam comprises a transverse electric field (TE) mode of the

optical beam.

11. (currently amended) A method, comprising:

directing a first optical beam into a coupling region defined in a semiconductor material

layer, the coupling region including an insulating region disposed between the first and second

optical waveguides in the semiconductor material layer;

coupling a first polarization mode of the first optical beam from the coupling region into

the first optical waveguide, the first optical waveguide including a first charge layer formed

proximate to the insulating region; and

coupling a second polarization mode of the first optical beam from the coupling region

into the second optical waveguide, the second optical waveguide including a second charge layer

formed proximate to the insulating region.

12. (original) The method of claim 11 wherein directing the first optical beam into the

coupling region comprises directing unpolarized light into the coupling region.

13. (original) The method of claim 11 further comprising:

directing a second optical beam having the first polarization mode through the first

optical waveguide into the coupling region;

directing a third optical beam having the second polarization mode through the second

optical waveguide into the coupling region; and

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combining the first polarization mode of the second optical beam with the second polarization mode of the third optical beam into unpolarized light directed from the coupling region.

14. (original) The method of claim 11 further comprising modulating an electric field across the insulating region disposed between the first optical waveguide and a second optical waveguide disposed in the semiconductor substrate layer to adjust a first coupling length for the first polarization mode of the optical beam directed into the coupling region and to adjust a second coupling length for the second polarization mode of the optical beam directed into the into the coupling region.

15. (original) The method of claim 11 further comprising:

modulating the first polarization mode of the first optical beam with a first optical modulator disposed in the semiconductor material layer; and

modulating the second polarization mode of the second optical beam with a second optical modulator disposed in the semiconductor material layer.

16. (original) The method of claim 15 further comprising combining the modulated first polarization mode of the first optical beam with the modulated second polarization mode of the first optical beam into a modulated first optical beam.

17. (original) The method of claim 16 wherein combining the modulated first polarization mode of the first optical beam with the modulated second polarization mode of the first optical beam into the modulated first optical beam comprises:

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directing the modulated first polarization mode of the first optical beam through the first optical waveguide into a second coupling region defined in the semiconductor material layer, the second coupling region including a second insulating region disposed between the first and second optical waveguides in the semiconductor material layer;

directing the modulated second polarization mode of the first optical beam through the second optical waveguide into the second coupling region.

18. (cancelled)

19. (currently amended) An apparatus, comprising:

a first polarization beam splitter/combiner through which an optical beam is to be directed;

a first optical modulator coupled to the first polarization beam splitter/combiner to receive a first polarization mode of the optical beam;

a second optical modulator coupled the first polarization beam splitter/combiner to receive a second polarization mode of the optical beam; and

a second polarization beam splitter/combiner coupled to the first and second optical modulators to receive and combine modulated first and second polarization modes, respectively, of the optical beam into a modulated optical beam, the first and second polarization beam splitters and the first and second optical modulators disposed in a semiconductor material layer,

wherein each of the first and second polarization beam splitters/combiners comprises:

a first optical waveguide disposed in the semiconductor material layer, the first optical waveguide including a first charge layer;

a second optical waveguide disposed in the semiconductor material layer, the

second optical waveguide including a second charge layer; and

an insulating region disposed between the first and second optical waveguides to

provide a coupling region in the semiconductor material layer between the first and

second optical waveguides, the first charge layer and the second charge layer formed

proximate to the insulating region.

20. (currently amended) The apparatus of claim 19 wherein each of the first and second

polarization beam splitters/combiners comprises:

a first optical waveguide disposed in the semiconductor material layer;

a second optical waveguide disposed in the semiconductor material layer; and

a insulating region disposed between the first and second optical waveguides to provide a

coupling region in the semiconductor material layer between the first and second optical

waveguides, the coupling region having the coupling region has a first coupling length for the

first polarization mode of the optical beam directed through one of the first and second optical

waveguides into the coupling region, the coupling region having and the coupling region has a

second coupling length for a second polarization mode of the optical beam.

21. (currently amended) The apparatus of claim 19 wherein each of the first and second

polarization beam splitters/combiners further comprises modulated charge layers proximate to

the insulating region in the coupling region to claim 20 wherein the first and second charge layers

adjust the first and second coupling lengths.

Claims 22-27. (cancelled)

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28. (currently amended) A system, comprising:

an optical transmitter to output an optical beam;

an optical receiver coupled to receive the optical beam; and

an polarization insensitive optical modulator coupled between the optical transmitter and the optical receiver to modulate the optical beam, the polarization insensitive optical modulator including:

a first polarization beam splitter/combiner through which the optical beam is to be directed;

a first optical modulator coupled to the first polarization beam splitter/combiner to receive a first polarization mode of the optical beam;

a second optical modulator coupled the first polarization beam splitter/combiner to receive a second polarization mode of the optical beam; and

a second polarization beam splitter/combiner coupled to the first and second optical modulators to receive and combine modulated first and second polarization modes, respectively, of the optical beam into a modulated optical beam, the first and second polarization beam splitters and the first and second optical modulators disposed in a semiconductor material layer,

wherein each of the first and second polarization beam splitters/combiners comprises:

a first optical waveguide disposed in the semiconductor material layer, the first optical waveguide including a first charge layer;

a second optical waveguide disposed in the semiconductor material layer, the second optical waveguide including a second charge layer; and

an insulating region disposed between the first and second optical waveguides to provide a coupling region in the semiconductor material layer between the first and

second optical waveguides, the first charge layer and the second charge layer formed

proximate to the insulating region.

29. (currently amended) The system of claim 28 wherein each of the first and second

polarization beam splitters/combiners comprise:

a first optical waveguide disposed in the semiconductor material layer;

a second optical waveguide disposed in the semiconductor material layer; and

a insulating region disposed between the first and second optical waveguides to provide a

coupling region in the semiconductor material layer between the first and second optical

waveguides, the coupling region having wherein the coupling region has a first coupling length

for the first polarization mode of the optical beam directed through one of the first and second

optical waveguides into the coupling region, the coupling region having and the coupling region

has a second coupling length for a second polarization mode of the optical beam.

30. (currently amended) The system of claim 29 wherein-each of the first and second

polarization beam splitters/combiners further comprises modulated charge layers proximate to

the insulating region in the coupling region to the first and second charge layers adjust the first

and second coupling lengths.

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